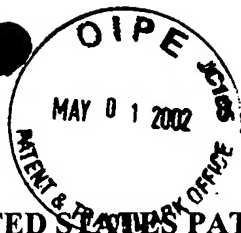


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PATENT

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5.14.02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : NIINISTÖ et al. Group Art Unit: 1762
Appl. No. : 10/067,634
Filed : February 4, 2002
For : METHOD OF DEPOSITING
RARE EARTH OXIDE THIN
FILMS
Examiner : Unknown

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SECOND PRELIMINARY AMENDMENT

UNITED STATES PATENT AND TRADEMARK OFFICE
P.O. Box 2327
Arlington, VA 22202

Dear Sir:

Prior to examination on the merits, please amend the above-identified application as follows.

In the Specification:

Please insert the following paragraph on page 1, following the title:

B₁
The present application claims priority to Japanese patent application number 2001-236874, filed August 3, 2001.

In the Claims:

Please cancel Claims 1-14 and add the following new claims:

B₂
15. (New) An atomic layer deposition (ALD) process for depositing rare earth metal oxide thin films on a substrate in a reaction space, comprising the steps of:

05/02/2002 501RETR1 00000003 10067634

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